

## Electronic Patent Application Fee Transmittal

<b>Application Number:</b>	10568126			
<b>Filing Date:</b>	14-Feb-2006			
<b>Title of Invention:</b>	Positive photoresist composition and resist pattern formation			
<b>First Named Inventor/Applicant Name:</b>	Yasuo Masuda			
<b>Filer:</b>	Neil S. Bartfeld/L. Racquel Raymond			
<b>Attorney Docket Number:</b>	SHIGA7045APC			
Filed as Large Entity				
<b>U.S. National Stage under 35 USC 371 Filing Fees</b>				
<b>Description</b>	<b>Fee Code</b>	<b>Quantity</b>	<b>Amount</b>	<b>Sub-Total in USD(\$)</b>
<b>Basic Filing:</b>				
<b>Pages:</b>				
<b>Claims:</b>				
<b>Miscellaneous-Filing:</b>				
<b>Petition:</b>				
<b>Patent-Appeals-and-Interference:</b>				
<b>Post-Allowance-and-Post-Issuance:</b>				
<b>Extension-of-Time:</b>				

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Miscellaneous:				
Request for continued examination	1801	1	790	790
Total in USD (\$)				790